

AMENDMENT TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

12. (Canceled)

13. (Canceled)

14. (Previously Presented): A surface treating apparatus according to claim 21, wherein said vapor deposition controlling gas is hydrogen.

15. (Previously Presented): A surface treating apparatus according to claim 21, wherein the molar ratio of said vapor deposition controlling gas to oxygen in at least the space between said melting/evaporating source and said work within said treating chamber can be adjusted by the feed rate of said vapor-depositing material fed from said feed reel.

16. (Canceled)

21. (Currently Amended): A surface treating apparatus comprising:
a treating chamber connected to an evacuating system;
a melting /evaporating source for melting and evaporating the wire-shaped vapor-depositing material containing a vapor deposition controlling gas, disposed in the treating chamber;

a rotatable cage-shaped, work retaining member, disposed in the treating chamber, and spaced above the melting/ evaporating source, for retaining a work on which the vapor depositing material is deposited; and

a supply of wire-shaped vapor-depositing material containing a predetermined amount of the vapor deposition controlling gas wound about a feed reel;

the feed reel being a horizontally disposed feed reel arranged such that the direction of winding of the wire-shaped vapor-depositing material containing the vapor disposition controlling gas on the feed reel is perpendicular to the direction of feeding of the wire-shaped vapor-depositing material containing the vapor deposition controlling gas to supply the wire-shaped vapor-depositing material containing the vapor deposition controlling gas to the melting/evaporating source, disposed in the treating chamber below the melting/evaporating source.